

IN THE CLAIMS:

Please amend the claims as follows:

1. (Currently amended) A lower shield adapted to be fastened to a body of a substrate support member in a plasma processing chamber having an upper annular shield coupled to the chamber's lip or walls, comprising:

a center portion having a first surface facing the body of the support member and a second surface opposite the first surface;

a bore disposed at least partially through the center portion and having a sidewall;

a groove disposed in the sidewall; and

a lip projecting from the first surface ~~of a portion of the center portion~~, the lip configured to maintain a spaced-apart relation from the body of the substrate support member.

2. (Original) The lower shield of claim 1, wherein the center portion further comprises a plurality of mounting holes and a plurality of lift pin holes disposed therethrough.

3. (Original) The lower shield of claim 1 further comprising at least one threaded hole adapted to receive an RF return strap electrically coupled to the shield.

4. (Currently amended) The lower shield of claim 1, wherein the lip further comprises at least one threaded hole adapted to receive a an RF return strap.

5. (Original) The lower shield of claim 1 further comprising:

a mounting ring disposed on the second surface and having an inner diameter;
and

a mounting surface formed in the mounting ring and orientated tangentially to the inner diameter.

6. (Currently amended) The lower shield of claim 5, wherein the mounting surface further comprises at least one threaded hole adapted to receive a an RF return strap.

7. (Currently amended) The lower shield of claim 1, wherein the lip and center portion are at least partially comprised of aluminum or at least partially coated with aluminum.

8. (Currently amended) The lower shield of claim 1, wherein the lip has circumscribes a diameter greater than a an outer diameter defined by a lower end of the upper annular shield.

9. (Currently amended) A An RF return lower shield for use in a plasma processing chamber having a substrate support member disposed inwards of an annular shield coupled to the chamber's walls, comprising:

- a an RF conductive center portion having a first surface and a second surface opposite the first surface;

- a bore disposed at least partially through the center portion and having a sidewall;

- a groove disposed in the sidewall;

- a an RF conductive lip projecting from the first surface ~~of a portion of the center portion~~, the lip configured to maintain a spaced-apart relation from the substrate support member;

- a mounting ring disposed on the second surface and having an inner diameter;

- a mounting surface formed in the mounting ring and orientated tangentially to the inner diameter and

- at least one threaded hole disposed in the mounting surface adapted to receive a RF return strap.

10. (Original) The lower shield of claim 9, wherein the mounting center portion further comprises a plurality of mounting holes and lift pin holes disposed therethrough.
11. (Original) The lower shield of claim 9 further comprising an aperture extending through the center portion concentrically disposed inward of the bore.
12. (Currently amended) A replaceable process kit for a processing chamber, the kit comprising:
a conductive, annular upper shield having a cylindrical portion terminating in an end having circumscribing a first diameter; and
a conductive lower shield comprising:
a center portion having a first surface facing the end circumscribing the first diameter and a second surface opposite the first surface;
a lip projecting from the first surface ~~of a portion of the center portion~~ and having circumscribing a diameter greater than a the first diameter ~~of the end of the cylindrical portion of the shield~~, the lip configured to maintain a spaced-apart relation from the ~~substrate support member~~ annular upper shield, and wherein the annular upper shield and the conductive lower shield are adapted to be disposed in the spaced-apart relation wherein the annular upper shield does not intersect a plane defined by the first surface.
13. (Original) The kit of claim 12, wherein the lower shield further comprises:
a bore disposed at least partially through the center portion and having a sidewall; and
a groove disposed in the sidewall.
14. (Original) The kit of claim 12, wherein the center portion further comprises a plurality of mounting holes and a plurality of lift pin holes disposed therethrough.

15. (Currently amended) The kit of claim 12, wherein the lower shield further comprises at least one threaded hole adapted to receive an RF return strap electrically coupled to the annular upper shield.

16. (Currently amended) The lower shield of claim 12, wherein the lower shield further comprises:

a mounting ring disposed on the second surface and having an inner diameter;
and

a mounting surface formed in the mounting ring and orientated tangentially to the inner diameter.

17. (Currently amended) The kit of claim 12, wherein the lower shield and/or upper shield are at least partially comprised of aluminum or at least partially coated with aluminum.

IN THE DRAWINGS:

As requested by the Examiner, Figure 2 has been amended to delete one inclusion of a twice designated reference numeral (292), and reference numeral 242 has been substituted therefor in accordance with the specification. Applicants submit that no new matter has been added.

Attachment: **Replacement Sheet**
 Annotated Sheet Showing Changes